

# Systems, Methods and Apparatus of a Low Conductance Silicon Micro-Leak for Mass Spectrometer Inlet

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## DESCRIPTION

This technology is a method for fabricating silicon micro-leak structure. The method involves fabricating channels in the micro-leak structure by several semiconductor processing tools. The substrates made of silicon and pyrex are provided in the micro-leak structure. The micro-leak structure is mounted in an inlet of a tube of a gaseous sampling device. The inlet holes and outlet holes are provided in the substrate.

## FEATURES AND BENEFITS

- The clogging of single channel with the particle is prevented.
- The number of components required for fabricating the silicon micro-leak structure is reduced.

## APPLICATIONS

- Atmospheric Sampling
- Spaceflight Mass Spectrometer
- Portable Instruments
- Homeland Security
- Point of Care Diagnostics

## FOR MORE INFORMATION

If you are interested in more information or want to pursue transfer of this technology, GSC-15341-1, please contact:

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